Updated Search Results Case No. 10/087,601				
(object adj area) and (image adj area)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB			
(((object adj area) and (image adj area)) and (focusing adj lens\$2)) and (deflect\$4 adj lens\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			
((object adj area) and (image adj area)) and (focusing adj lens\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			
(((object adj area) and (image adj area)) and (focusing adj lens\$2)) and deflect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB			
focus\$3 with lens\$2 with first	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB			
(first adj focus\$3 adj lens) and (second adj focus\$3 adj lens)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			
(359/619,622,637,558).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB			
(430/5,22,30,322,296).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			
(250/492.22,492.1).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			
(702/126,40).CCLS.				
(204/157.68,456).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			
((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			
(((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and (electron\$1 with (project\$4 or imag\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			
(((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and (electron\$1 with beam\$1 with (project\$4 or imag\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB			

.

(((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and (electron\$1 with beam\$1 with (project\$4 or imag\$3 or deflect\$4)) (((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB  USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
(((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and (focus\$3 with lens\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and (focus\$3 with lens\$2)) and object\$1 and image\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 with lens\$2) with (two or (first and second)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((((359/619,622,637,558).CCLS.) or ((430/5,22,30,322,296).CCLS.) or ((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 with lens\$2) same first same second)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

((((350)610 622 637 558) CCI S \ or	USPAT; US-PGPUB;
(((359/619,622,637,558).CCLS.) or	i '
((430/5,22,30,322,296).CCLS.) or	EPO; JPO; DERWENT;
((250/492.22,492.1).CCLS.) or	IBM_TDB
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))	
and ((electron\$1 or particle\$1) with beam\$1 with	
(project\$4 or imag\$3 or deflect\$4 or variable))) and	
((focus\$3 with lens\$2) with two)	
((((359/619,622,637,558).CCLS.) or	USPAT; US-PGPUB;
((430/5,22,30,322,296).CCLS.) or	EPO; JPO; DERWENT;
(250/492.22,492.1).CCLS.) or	IBM_TDB
(702/126,40).CCLS.) or ((204/157.68,456).CCLS.))	_
and ((electron\$1 or particle\$1) with beam\$1 with	
(project\$4 or imag\$3 or deflect\$4 or variable))) and	
((focus\$3 adj lens\$2) with two)	
The state of the s	
((((359/619,622,637,558).CCLS.) or	USPAT; US-PGPUB;
((430/5,22,30,322,296).CCLS.) or	EPO; JPO; DERWENT;
(250/492.22,492.1).CCLS.) or	IBM_TDB
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))	
and ((electron\$1 or particle\$1) with beam\$1 with	
(project\$4 or imag\$3 or deflect\$4 or variable))) and	
((focus\$3 adj lens\$2) with two)	
((loodeqo daj lolleq=) w.a. two)	
((((359/619,622,637,558).CCLS.) or	USPAT; US-PGPUB;
((430/5,22,30,322,296).CCLS.) or	EPO; JPO; DERWENT;
· ·	1
((250/492.22,492.1),CCLS.) or	IBM_TDB
, ,	<del>-</del>
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.))	<del>-</del>
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with	<del>-</del>
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and	<del>-</del>
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and	<del></del>
((250/492.22,492.1).CCLS.) or ((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)	<del></del>
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)	
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)	USPAT; US-PGPUB; EPO; JPO; DERWENT;
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second) ((359/283).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB;
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)  ((359/283).CCLS.)  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB;
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second) ((359/283).CCLS.) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)  ((359/283).CCLS.)  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))  ((359/283).CCLS.) and ((electron\$1 or particle\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB;
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)  ((359/283).CCLS.)  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))  ((359/283).CCLS.) and ((electron\$1 or particle\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)  ((359/283).CCLS.)  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4) with (project\$4 or imag\$3 or deflect\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)  ((359/283).CCLS.)  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4) with (project\$4 or imag\$3 or deflect\$4) with (project\$4 or imag\$3 or deflect\$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB;
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)  ((359/283).CCLS.)  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4) with (project\$4 or imag\$3 or deflect\$4) with (project\$4 or imag\$3 or deflect\$4 or variable))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second)  ((359/283).CCLS.)  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4 or variable))  ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4 or variable))  ((359/619,622,637,558).CCLS.) or ((359/283).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second) ((359/283).CCLS.) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable)) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4 or variable)) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4 or variable)) ((359/619,622,637,558).CCLS.) or (((359/283).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; USPAT; US-PGPUB;
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second) ((359/283).CCLS.) ((359/283).CCLS.) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable)) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4 or variable)) ((359/283).CCLS.) and ((electron\$1 or particle\$1)) (((359/619,622,637,558).CCLS.) or ((359/283).CCLS.)) (((((359/283).CCLS.))) and ((electron\$1 or particle\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
((702/126,40).CCLS.) or ((204/157.68,456).CCLS.)) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with second) ((359/283).CCLS.) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable)) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4 or variable)) ((359/283).CCLS.) and ((electron\$1 or particle\$1) with (project\$4 or imag\$3 or deflect\$4 or variable)) ((359/619,622,637,558).CCLS.) or (((359/283).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

\*

((((359/619,622,637,558).CCLS.) or ((359/283).CCLS.)) and ((electron\$1 or particle\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT		
with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))) and ((focus\$3 adj lens\$2) with			
second)			
(((359/619,622,637,558).CCLS.) or	USPAT; US-PGPUB;		
((359/283).CCLS.)) and ((electron\$1 or particle\$1)	EPO; JPO; DERWENT		
with beam\$1 with (project\$4 or imag\$3 or deflect\$4 or variable))	IBM_TDB		
((electron\$1 or particle\$1) with beam\$1 with	USPAT; US-PGPUB;		
(project\$4 or imag\$3 or deflect\$4 or variable))	EPO; JPO; DERWENT		
("5260151").PN.	USPAT		
("5376505").PN.	USPAT		
("5079112").PN.	USPAT		
("5316879").PN.	USPAT		
("5130213").PN.	USPAT		
("5258246").PN.	USPAT		
scalpel	USPAT; US-PGPUB;		
	EPO; JPO; DERWENT		
	IBM_TDB		
scalpel and (focus\$3 with lens\$2)	USPAT; US-PGPUB;		
	EPO; JPO; DERWENT		
	IBM_TDB		
scalpel and ((electron\$1 or particle\$1) with	USPAT; US-PGPUB;		
(project\$4 or imag\$3 or deflect\$4 or variable))	EPO; JPO; DERWENT		
	IBM_TDB		
(scalpel and (focus\$3 with lens\$2)) and (scalpel	USPAT; US-PGPUB;		
and ((electron\$1 or particle\$1) with (project\$4 or	EPO; JPO; DERWENT		
imag\$3 or deflect\$4 or variable)))	IBM_TDB		
(scalpel and ((electron\$1 or particle\$1) with	USPAT; US-PGPUB;		
(project\$4 or imag\$3 or deflect\$4 or variable))) and	EPO; JPO; DERWENT		
((focus\$3 with lens\$2) same first same second)	IBM_TDB		
(scalpel and ((electron\$1 or particle\$1) with	USPAT; US-PGPUB;		
(project\$4 or imag\$3 or deflect\$4 or variable))) and	EPO; JPO; DERWENT		
((focus\$3 with lens\$2) with two)	IBM_TDB		
((scalpel and ((electron\$1 or particle\$1) with	USPAT; US-PGPUB;		
(project\$4 or imag\$3 or deflect\$4 or variable))) and	EPO; JPO; DERWENT		
((focus\$3 with lens\$2) same first same second) ) or	IBM_TDB		
((scalpel and ((electron\$1 or particle\$1) with			
(project\$4 or imag\$3 or deflect\$4 or variable))) and			
((focus\$3 with lens\$2) with two))			
(((scalpel and ((electron\$1 or particle\$1) with	USPAT; US-PGPUB;		
(project\$4 or imag\$3 or deflect\$4 or variable))) and	EPO; JPO; DERWENT		
((focus\$3 with lens\$2) same first same second)) or	•		
((scalpel and ((electron\$1 or particle\$1) with	<b>-</b>		
(project\$4 or imag\$3 or deflect\$4 or variable))) and			
·· -	1		
((focus\$3 with lens\$2) with two) )) and deflect\$4			

,

## Search Results Case No. 10/087,601

US 6280906 B1	USPAT	Method of imaging a mask pattern on a substrate by means of EUV radiation, and apparatus and mask for performing the method	430/296
US 6355384 B1	LICDAT	Mask, its method of formation, and a	430/5
US 6355364 BT	USPAT	semiconductor device made thereby	430/5
US 6090527 A	USPAT	Electron beam exposure mask and method of manufacturing the same and electron beam exposure method	430/296
US 5520297 A	USPAT	Aperture plate and a method of manufacturing the same	216/12
US 5849437 A	USPAT	Electron beam exposure mask and method of manufacturing the same and electron beam exposure method	430/5
US 6326629 B1	USPAT	Projection lithography device utilizing charged particles	250/492.2
US 6171736 B1	USPAT	Projection-microlithography alignment method utilizing mask with separate mask substrates	430/22
US 6180289 B1	USPAT	Projection-microlithography mask with separate mask substrates	430/5
US 6124596 A	USPAT	Charged-particle-beam projection apparatus and transfer methods	250/396ML
US 5466904 A	USPAT	Electron beam lithography system	219/121.25
US 5973333 A	USPAT	Charged-particle-beam pattern-transfer apparatus and methods	250/492.23